



Cite this: *Nanoscale*, 2023, **15**, 17765

Received 7th September 2023,  
Accepted 19th October 2023

DOI: 10.1039/d3nr04521h

rsc.li/nanoscale

## A comparative investigation of the chemical reduction of graphene oxide for electrical engineering applications†

Tomasz Chudziak,<sup>a,b</sup> Verónica Montes-García,<sup>b,c</sup> Włodzimierz Czepa,<sup>a,b</sup> Dawid Pakulski,<sup>b</sup> Andrzej Musiał,<sup>b,d</sup> Cataldo Valentini,<sup>b</sup> Michał Bielejewski,<sup>b,d</sup> Michela Carlin,<sup>e</sup> Aurelia Tubaro,<sup>e</sup> Marco Pelin,<sup>e</sup> Paolo Samori<sup>b,c</sup> and Artur Ciesielski<sup>b,c</sup>\*

The presence of oxygen-containing functional groups on the basal plane and at the edges endows graphene oxide (GO) with an insulating nature, which makes it rather unsuitable for electronic applications. Fortunately, the reduction process makes it possible to restore the sp<sup>2</sup> conjugation. Among various protocols, chemical reduction is appealing because of its compatibility with large-scale production. Nevertheless, despite the vast number of reported chemical protocols, their comparative assessment has not yet been the subject of an in-depth investigation, rendering the establishment of a structure–performance relationship impossible. We report a systematic study on the chemical reduction of GO by exploring different reducing agents (hydrazine hydrate, sodium borohydride, ascorbic acid (AA), and sodium dithionite) and reaction times (2 or 12 hours) in order to boost the performance of chemically reduced GO (CrGO) in electronics and in electrochemical applications. In this work, we provide evidence that the optimal reduction conditions should vary depending on the chosen application, whether it is for electrical or electrochemical purposes. CrGO exhibiting a good electrical conductivity (>1800 S m<sup>-1</sup>) can be obtained by using AA (12 hours of reaction), Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub> and N<sub>2</sub>H<sub>4</sub> (independent of the reaction time). Conversely, CrGO displaying a superior electrochemical performance (specific capacitance of 211 F g<sup>-1</sup>, and capacitance retention >99.5% after 2000 cycles) can be obtained by using NaBH<sub>4</sub> (12 hours of reaction). Finally, the compatibility of the different CrGOs with

wearable and flexible electronics is also demonstrated using skin irritation tests. The strategy described represents a significant advancement towards the development of environmentally friendly CrGOs with *ad hoc* properties for advanced applications in electronics and energy storage.

## Introduction

Graphene oxide (GO) is one of the most widely studied two-dimensional materials (2DMs) due to its large-scale production at low cost and easy processing.<sup>1,2</sup> Oxygen-containing functional groups (OFGs) (hydroxyl, epoxy, carbonyl and carboxyl) present on the basal plane and the edges impart to GOs a unique set of physicochemical properties, such as good dispersibility and colloidal stability in many solvents, including water. Importantly, these OFGs can serve as active sites for chemical modification with multiple molecules, making GO a suitable material for application in the fields of chemical sensing,<sup>3</sup> energy storage,<sup>4</sup> water desalination,<sup>5</sup> drug delivery,<sup>6</sup> solar cells,<sup>7</sup> memory devices,<sup>8</sup> and healthcare<sup>9–11</sup> to name a few. However, the OFGs present in GO also disrupt the extended sp<sup>2</sup> network characteristic of graphene, resulting in an insulating material unsuitable for electricity-based applications.<sup>12</sup> Fortunately, such a limitation can be overcome to a great extent through the removal of OFGs from GO *via* reduction processes, enhancing the degree of conjugation in the carbon network through the formation of sp<sup>2</sup> species, ultimately boosting the electrical characteristics of the material.<sup>13</sup> In order to obtain the electroactive form of GO, named reduced graphene oxide (rGO), a variety of thermal (TrGO), chemical (CrGO), electrochemical,<sup>14,15</sup> sonification,<sup>16</sup> microwave,<sup>17</sup> and photo-assisted<sup>18</sup> methods have been explored, with TrGO and CrGO methodologies being the most extensively employed.<sup>19,20</sup>

On the one hand, thermal reduction represents one of the most attractive reduction methods due to its low environ-

<sup>a</sup>Faculty of Chemistry, Adam Mickiewicz University, Uniwersytetu Poznańskiego 8, Poznań, Poland

<sup>b</sup>Center for Advanced Technologies, Adam Mickiewicz University, Uniwersytetu Poznańskiego 10, Poznań, Poland. E-mail: ciesielski@unistra.fr

<sup>c</sup>University of Strasbourg CNRS ISIS UMR 7006, 8 Allée Gaspard Monge, F-67000 Strasbourg, France. E-mail: samori@unistra.fr

<sup>d</sup>Institute of Molecular Physics, Polish Academy of Sciences, M. Smoluchowskiego 17, 60-179 Poznań, Poland

<sup>e</sup>Department of Life Sciences, University of Trieste, Via Fleming 22, 34127 Trieste, Italy

†Electronic supplementary information (ESI) available. See DOI: <https://doi.org/10.1039/d3nr04521h>



mental impact. However, the high temperatures typically required to accomplish this process (above 1000 °C) are energetically demanding and are incompatible with the use of plastic substrates often desired for flexible electronic applications.<sup>21</sup> Recently, we have reported a systematic study on the low-temperature annealing of GO by optimizing different annealing conditions, *i.e.*, temperature, time and reduction atmosphere.<sup>4</sup> We have demonstrated that TrGO can be obtained under air or inert atmosphere at relatively low temperatures (<300 °C) exhibiting low film resistivities ( $10^{-2}$ – $10^{-4}$  Ωm) combined with unaltered resistance after 2000 bending cycles when supported on plastic substrates. Besides, TrGO electrodes displayed enhanced electrochemical performance, achieving a specific capacitance of 208 F g<sup>-1</sup> and a capacitance retention >99% after 2000 charge–discharge cycles.<sup>4</sup>

On the other hand, chemical reduction is currently the most efficient approach for reducing GO, approaching the electrical characteristics of graphene ( $8.5 \times 10^4$  S m<sup>-1</sup> is the highest electrical conductivity reported for CrGO).<sup>22</sup> Chemical reduction is appealing from the industrial point of view because of its compatibility with large-scale commercial production with low-energy consumption (temperature of reduction is usually below 100 °C). CrGO can be obtained by using a plethora of reducing agents including hydrazine hydrate (N<sub>2</sub>H<sub>4</sub>), dimethylhydrazine, *p*-phenylene diamine, ethylenediamine, hydroxylamine,<sup>23,24</sup> lithium aluminium hydride, sodium borohydride (NaBH<sub>4</sub>),<sup>25</sup> sodium bisulfite (NaHSO<sub>3</sub>), L-ascorbic acid (AA),<sup>26–28</sup> or sodium dithionite (Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>), among others.

However, a variety of reducing agents and protocols have been reported in the literature (Table S2, ESI<sup>†</sup>), making it quite difficult to assess and compare these strategies from the perspective of structure–performance relationship. For instance, for applications in electronics, CrGO with the highest electrical conductivity is desirable and therefore the removal of OFGs should be maximized. Unfortunately, some of the employed reducing agents or their oxidized forms may also result in doping or contamination of the CrGO. Although CrGO synthesized with hydrazine hydrate is usually considered to most closely resemble pristine graphene in terms of electronic and structural properties, it has been reported that films of CrGO synthesized using sodium borohydride have significantly lower sheet resistance. This result can be explained by CrGO contamination with nitrogen and pyrazole formation, where the nitrogen atoms behave as electron donors and supply p-type holes.<sup>25,29,30</sup> Ascorbic acid, which can be regarded as the most studied ‘green’ reducing agent to obtain CrGO, also suffers from the same contamination problem.<sup>26,28,31–33</sup> AA is oxidized first to dehydroascorbic acid (DHA) and then to oxalic and guluronic acids, both of which can supramolecularly interact with the unreacted carboxylic groups of pristine GO.<sup>34–36</sup>

In contrast to electrical applications, the scenario is not as straightforward when it comes to electrochemical energy storage applications.<sup>37,38</sup> As previously reported, OFGs contribute towards enhancing the electrochemical performance of pseudocapacitive rGO electrodes and their removal is always

detrimental to the device performance. For instance, ultra-high-level oxygen-functionalized GO (UHFGO) has shown an impressive capacitance of 285 F g<sup>-1</sup> in a gel electrolyte.<sup>39</sup> Alternative strategies such as heteroatom doping have also been widely employed to boost the electrochemical performance of pristine GO.<sup>40,41</sup> Nevertheless, the electrochemical performance of rGO electrodes is superior to that of pristine GO electrodes because the removal of OFGs is accompanied by other physicochemical and structural changes in rGO, such as an increase in conductivity, surface area and pore size. Therefore, the best reducing conditions for applications in electronics or in electrochemical energy storage may differ. To the best of our knowledge, there is no systematic study that compares the physicochemical and structural properties of CrGO with its performance in electronics or in electrochemical energy storage by using different reducing agents and reducing times. Furthermore, one of the major criticisms that chemical reduction has received is the use of toxic reducing agents. However, there has been limited discussion regarding the toxicity of the resulting CrGO.

To address this significant knowledge gap, we investigated the fine-tuning of the reduction degree of GO by varying the reduction conditions, specifically the choice of the reducing agent and reaction time (2 or 12 hours). Regarding reducing agents, we focused our attention on four of the most commonly employed ones, namely, hydrazine hydrate, sodium borohydride, ascorbic acid, and a sulphur-containing compound such as sodium dithionite.<sup>42,43</sup> Our study was aimed at systematically investigating how these factors influenced the toxicity and the physicochemical and structural properties of CrGO, ultimately boosting their performance for electronic devices or energy storage applications.

## Results and discussion

The chemical reduction of GO was firstly followed by Fourier-transform infrared (FTIR) spectroscopy (Fig. S1, ESI<sup>†</sup>). The black curve reveals the characteristic vibration bands of GO: 2500–3500 cm<sup>-1</sup> (OH, stretching vibration), 1722 cm<sup>-1</sup> (C=O, stretching vibration), 1620 cm<sup>-1</sup> (aromatic C=C, stretching vibration), 1400 cm<sup>-1</sup> (C–OH, bending vibration), 1220 cm<sup>-1</sup> and 1046 cm<sup>-1</sup> (breathing vibrations) and ~1000 cm<sup>-1</sup> (stretching vibrations from the epoxy, ether or peroxide groups).<sup>28,34,44</sup> After 2 hours of chemical reduction, the vibrations related to the different OFGs were significantly reduced in rGO(N<sub>2</sub>H<sub>4</sub>) and rGO(Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>). However, to observe the same reduction degree in rGO(AA) or rGO(NaBH<sub>4</sub>), 12 hours of reduction was needed. Based on the ratio of the C=C stretching vibration to any OFG vibration, FTIR analysis offered the first insight into the reduction strength of the four reducing agents explored, with N<sub>2</sub>H<sub>4</sub> and Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub> as the strongest reducing agents, then AA and finally NaBH<sub>4</sub> as the mildest reducing agent.

The degree of GO reduction is usually expressed by the C/O ratio obtained from X-ray photoelectron spectroscopy (XPS) analysis. However, as XPS is a surface-sensitive technique (*i.e.*,

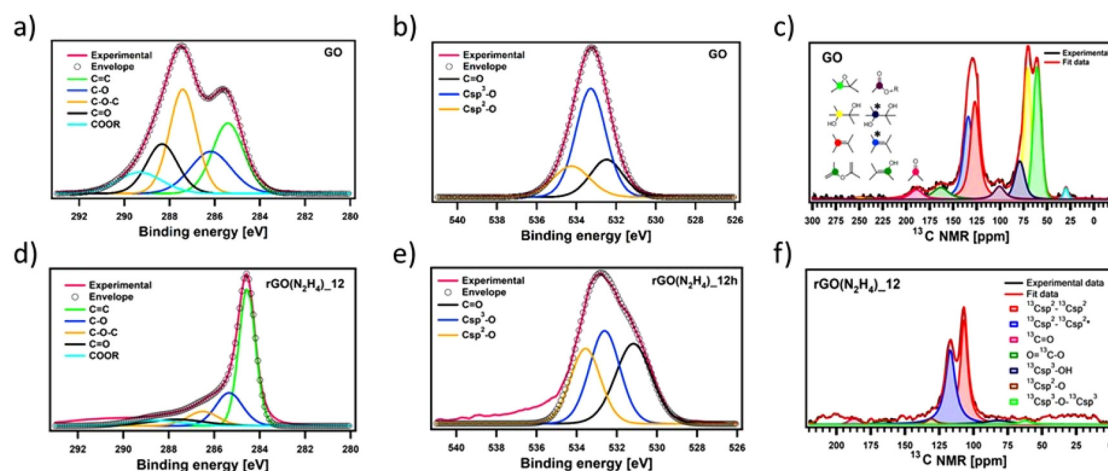


the penetration depth of the XPS beam ranges only between 1 and 10 nm), we firstly performed elemental analyses (E.A.) of chemically reduced GO (Table S3, ESI†). As can be seen in Table S3,† the C/O ratio ranges from 0.99 for pristine GO to 7.20 for rGO(N<sub>2</sub>H<sub>4</sub>)<sub>12</sub> h. According to the C/O ratio, the strength of the reducing agents varies as follows: Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub> ≈ N<sub>2</sub>H<sub>4</sub> > AA > NaBH<sub>4</sub>, in agreement with FTIR analyses. Interestingly, the nitrogen content is slightly higher in the samples reduced with N<sub>2</sub>H<sub>4</sub>, indicating a possible contamination from the reaction of GO with N<sub>2</sub>H<sub>4</sub> (e.g., pyrazole formation).

To gain insights into the chemical composition of CrGO, X-ray photoelectron spectroscopy (XPS) and solid-state NMR magic angle spinning (ssNMR-MAS) analyses were then performed on the GO and CrGO powders (Fig. 1–2 and Fig. S2–10, ESI†). From the XPS survey spectra (Fig. S2 and 3, ESI†), the C/O ratio was estimated (Table S4, ESI†), ranging from 0.86 for pristine GO up to 11.21 for rGO(Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>)<sub>12</sub> h. In full agreement with FTIR and E.A., the strength of the reducing agents followed the same trend. Likewise, the nitrogen element was also present in the rGO(N<sub>2</sub>H<sub>4</sub>) samples, and its amount was proportional to the reaction time (2.70% after 12 hours of reaction). Traces of sodium element (~1%) were found in the rGO(NaBH<sub>4</sub>) samples, but were not sufficient to be detected in elemental analysis. No contamination of sodium or sulfur was observed in the rGO(Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>) samples. Regarding the reaction time, a negligible difference (i.e., max. 5% of increase) was obtained between 2 and 12 hours of reaction for all the reducing agents. Although FTIR, E.A. and XPS survey spectra showed the same tendency in the strength of the reducing agents, a deeper analysis was needed to unveil the influence of the reaction time. To cast light onto the chemistry of the reduction process by each reducing agent, the high resolution C 1s and O 1s XPS and ssNMR-MAS spectra were deconvoluted as previously reported by us.<sup>4</sup> The high resolution C 1s spectra were fitted using 5 Gaussian–Lorentzian curves for the 5

chemical environments: 284.5 eV C–C (C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub>), 285.15 eV C–O (including C<sub>sp<sup>2</sup></sub>–O–C<sub>sp<sup>2</sup></sub>, C<sub>sp<sup>3</sup></sub>–OH and C<sub>sp<sup>2</sup></sub>–OH), 286.5 eV C–O–C (C<sub>sp<sup>3</sup></sub>–O–C<sub>sp<sup>3</sup></sub>), 287.40 eV C=O, and 288.50 eV COOR (including COOH and lactone) (Fig. 1(a), (d) and Fig. S4, ESI†).<sup>4</sup> Likewise, the high resolution O 1s spectra were fitted with 3 Gaussian–Lorentzian curves: 531.08 eV C=O, 532.03 eV C<sub>sp<sup>3</sup></sub>–O (including C<sub>sp<sup>3</sup></sub>–O–C<sub>sp<sup>3</sup></sub>, and C<sub>sp<sup>3</sup></sub>–OH), and 533.43 eV C<sub>sp<sup>2</sup></sub>–O (including C<sub>sp<sup>2</sup></sub>–O–C<sub>sp<sup>2</sup></sub> and C<sub>sp<sup>2</sup></sub>–OH) (Fig. 1(b), (e) and Fig. S5, ESI†).<sup>4</sup> To complete the analysis, the ssNMR-MAS spectra were deconvoluted in eight curves: 60.4 ppm (<sup>13</sup>C<sub>sp<sup>3</sup></sub>–O–<sup>13</sup>C<sub>sp<sup>3</sup></sub>), 70.6 ppm (<sup>13</sup>C<sub>sp<sup>3</sup></sub>–OH), 78.9 ppm (<sup>13</sup>C<sub>sp<sup>3</sup></sub>–OH, close to defects), 100.2 ppm (<sup>13</sup>C–OOR), 126.7 ppm (<sup>13</sup>C<sub>sp<sup>2</sup></sub>–<sup>13</sup>C<sub>sp<sup>2</sup></sub>), 134.7 ppm (<sup>13</sup>C<sub>sp<sup>2</sup></sub>–<sup>13</sup>C<sub>sp<sup>2</sup></sub> close to defects), 162.4 ppm (C<sub>sp<sup>2</sup></sub>–O (including C<sub>sp<sup>2</sup></sub>–O–C<sub>sp<sup>2</sup></sub> and C<sub>sp<sup>2</sup></sub>–OH)) and 187.9 ppm (<sup>13</sup>C=O) (Fig. 1(c), (f) and Fig. S8, ESI†). Fig. 1 shows the deconvolution of the C 1s and O 1s XPS and ssNMR-MAS spectra for GO (Fig. 1(a–c)) and as representative CrGO, we show analogous results using rGO(N<sub>2</sub>H<sub>4</sub>)<sub>12</sub> h (Fig. 1(d–f)). The results for all the reducing agents and reaction times can be seen in the ESI (Fig. S4–5 and S8†).

Fig. S7 and S9 (ESI†) show the evolution of the area of each component in XPS (Fig. S7, ESI†) and ssNMR spectra (Fig. S9, ESI†) as a function of the reducing agents and reaction time. However, for a straightforward analysis, we divided the components into three groups, (i) C=C (Fig. S10, ESI†), (ii) C=O (Fig. 2(a–c)) and (iii) C–O (Fig. 2(d–f)). As expected, the area of the C=C (Fig. S10(a), ESI†) and C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub> (Fig. S10(b), ESI†) peaks increased in all the cases as the reduction process restored the π-conjugation of the carbon sheets. While the largest C=C and C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub> peak areas were obtained for rGO(Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>)<sub>2</sub> h, the smallest C=C and C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub> peak areas were observed for rGO(NaBH<sub>4</sub>)<sub>2</sub> h. The reaction time only played a major role when NaBH<sub>4</sub> was used as a reducing agent. The area of C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub> close to the defects (C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub>\*) increased with the reduction process. Interestingly, we observed a decrease of the C<sub>sp<sup>2</sup></sub>–C<sub>sp<sup>2</sup></sub>\* peak area after 12 hours of reaction



**Fig. 1** Fitted XPS (a and d) C 1s and (b and e) O 1s spectra of (a and b) GO and (d and e) CrGO with hydrazine for 12 hours of reaction time and their corresponding chemical groups; (c and f) fitted ssNMR spectra of (c) GO and (f) CrGO with N<sub>2</sub>H<sub>4</sub> for 12 hours of reaction time and their corresponding chemical groups. The stars refer to the chemical groups close to defects.





the restoration of  $sp^2$  conjugation due to the removal of the oxygen functional groups from GO.<sup>50,51</sup> The increase in the  $I_D/I_G$  ratio is proportional to the strength of the reducing agent, in full agreement with previous characterization results. In addition, the  $I_D/I_G$  ratio decreases after 12 hours of reaction when AA and  $N_2H_4$  are employed, which is related to undesired contamination. The additional bands (D', D\* and D') arise from the defects present in the graphitic structure of the carbon material.<sup>48,52–54</sup> The  $I_{D'}/I_G$ ,  $I_{D^*}/I_G$ , and  $I_D/I_G$  ratios are shown in Fig. S13(b), (c) and (d) (ESI†), respectively. Ideally, all these ratios should decrease with the reduction degree but as we can see, the  $I_D/I_G$  and  $I_{D'}/I_G$  ratios increased slightly in all the cases; therefore, it can be concluded that the chemical reduction process creates defects in the graphitic structure of the carbon material. In contrast, the  $I_{D^*}/I_G$  ratio decreases in all the cases and the decrease is proportional to the strength of the reducing agent.

To unravel the number of defects present in the pristine GO and CrGO we followed the protocol reported by Cançado *et al.*<sup>51</sup> First, we calculated the average defect distance ( $L_D$ ) by using eqn (2) (see the Materials and characterization section in the ESI† for details). As shown in Fig. S14(a),† the  $L_D$  of pristine GO amounts to  $9.64 \pm 1.11$ , which upon reduction only decreases slightly to  $8.27 \pm 0.95$  for the strongest reducing conditions (rGO( $Na_2S_2O_4$ )\_12 h). As  $L_D \approx 10$ , we estimated the number of defects in each case by using eqn (3) (see the Materials and characterization section in the ESI† for details). Fig. S14(b)† shows that the number of defects in GO and CrGO is between  $7.8 \times 10^{10}$  and  $10.6 \times 10^{10}$ .

The effect of the different reducing agents on the crystallinity of CrGO was investigated using powder X ray diffraction (PXRD) (Fig. 3). The pristine GO diffraction pattern displays one characteristic peak at  $2\theta = \sim 10^\circ$  (peak I) with a Full-Width at Half Maximum (FWHM) of  $0.81^\circ$  related to the (002) family of planes (Fig. 3). After the chemical reduction, the CrGO exhibits one characteristic peak at  $2\theta = \sim 25^\circ$  (peak II), with a larger FWHM of  $4.4$ – $5.81^\circ$ , related to the smaller crystallite sizes and a second at about  $42.8^\circ$  related to the (100) family of planes. Fig. 3 shows that after two hours of reaction peak I completely disappears when  $Na_2S_2O_4$ ,  $N_2H_4$  and AA reducing agents are used. However, peak I is still present even after 12 hours of reaction when  $NaBH_4$  is used, which is in agreement with the results obtained by Shin *et al.*<sup>25</sup> From the scattering angle ( $2\theta$ ) of each peak we can quantify the  $d$ -spacing, average crystalline size ( $L_a$ ), crystalline thickness ( $L_c$ ), and graphene layer number ( $n$ ) for GO and all CrGO using the Debye–Scherrer equation (Fig. 3(c) and Table S5, ESI†). The  $d$ -spacing of pristine GO amounts to  $8.79 \text{ \AA}$  and after its chemical reduction, it decreased to  $\sim 3.76 \text{ \AA}$ .<sup>55,56</sup> The considerable shrinkage of the interlayer distance is connected to the partial removal of the OFGs from the GO sheets. The  $d$ -spacing slightly decreases with the reaction time but no major differences are found between the reducing agents employed. The crystal thickness ( $L_c$ ) considerably decreases from  $97.32 \text{ \AA}$  of pristine GO to  $\sim 15.5 \text{ \AA}$  after its chemical reduction. Interestingly, no major differences are found between the reducing agents and reac-

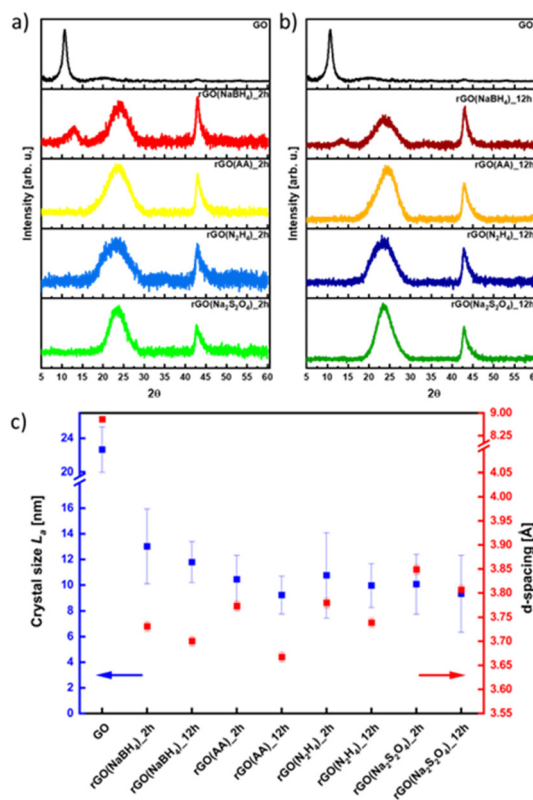


Fig. 3 XRD patterns of rGO reduced for (a) 2 hours and (b) 12 hours, and (c) dependence on crystal size ( $L_a$ ) and  $d$ -spacing in correlation with the reducing agent.

tion time for both  $L_c$  and  $L_a$  (Fig. 3(c) and Table S5, ESI†). Remarkably, the theoretical number of layers ( $n_c$ ) reveals that few layer-thick CrGO sheets (3–5 layers) can be produced even with mild reducing agents like AA. Therefore, we can conclude that the choice of the reducing agent and reaction time have no strong influence on the crystallinity of the resulting CrGO.

Scanning electron microscopy (SEM) images (Fig. S15 and 16, ESI†) reveal the absence of morphological changes upon the chemical reduction of GO for all the reducing agents and reaction times employed. Thermogravimetric analysis (TGA) was then performed to evaluate the thermal stability of CrGO (Fig. S17, ESI†). As shown in Fig. S17 (ESI†), the thermal stability of GO increased upon chemical reduction and the  $T_{d10}$  (thermal decomposition of 10% weight) increased from  $70^\circ \text{C}$  (pristine GO) to  $430^\circ \text{C}$  in the case of  $Na_2S_2O_4$  and  $N_2H_4$  and to  $450^\circ \text{C}$  in the case of AA and  $NaBH_4$ . Two main conclusions can be drawn from the TGA analysis: in agreement with the previous characterization results, no major differences were found between the two reaction times studied and the thermal stability of CrGO was the highest for the samples with the highest C/O ratio and therefore characterized by a greater  $C_{sp^2}$  content.

The specific surface area and average pore size of CrGO were evaluated by recording  $N_2$  adsorption–desorption isotherms at  $77 \text{ K}$  (Fig. S18–21, ESI†). The adsorption isotherms



of the CrGO exhibited type-I sorption isotherms, with steep rises appearing at low relative pressure and type-IV sorption features with adsorption/desorption hysteresis at higher pressure. The calculated Brunauer–Emmett–Teller (BET) surface area of CrGO revealed significant differences between the reducing agents used (Fig. S22(a), ESI†). In all the cases, the surface area increased with the reaction time (between 25 and 97% increase). Interestingly, the two reducing agents that produced CrGO with the highest C/O ratio ( $\text{Na}_2\text{S}_2\text{O}_4$  and  $\text{N}_2\text{H}_4$ ), exhibited the lowest surface areas ( $140.91$  and  $96.41$   $\text{m}^2$   $\text{g}^{-1}$ , respectively, after 2 hours of reaction). In contrast, when the mildest reducing agents AA and  $\text{NaBH}_4$  were used, CrGO exhibited the highest surface areas ( $394.90$  and  $555.63$   $\text{m}^2$   $\text{g}^{-1}$ , respectively, after 12 hours of reaction) compared to pristine GO ( $12.61$   $\text{m}^2$   $\text{g}^{-1}$ ). The same trends were observed for the average pore size of CrGO (Fig. S22(b), ESI†), ranging from  $1.40$  nm when  $\text{Na}_2\text{S}_2\text{O}_4$  was used for 2 hours of reaction time, to  $13.70$  nm when AA was used for 12 hours of reaction time.

To gain a greater insight into the electrical performance of CrGO, thin film conductivity measurements were performed. Pellets of different materials were prepared (see the ESI†) and the film resistivity was measured with a four-point probe (FPP) (Fig. S23, ESI†). Due to its insulating character, the film resistivity of the pristine GO material was above our instrument's detection limit. The film conductivity of CrGO, ranging from  $2.7 \times 10^1$   $\text{S m}^{-1}$  ( $\text{rGO}(\text{NaBH}_4)_2$  h) to  $4.3 \times 10^3$   $\text{S m}^{-1}$  ( $\text{rGO}(\text{Na}_2\text{S}_2\text{O}_4)_2$  h), gradually increased with the strength of the employed reducing agent, following a trend in full agreement with the previous characterization results. Therefore, for electrical applications,  $\text{rGO}(\text{AA})_{12}$  h,  $\text{rGO}(\text{Na}_2\text{S}_2\text{O}_4)$  and  $\text{rGO}(\text{N}_2\text{H}_4)$  represent the best choices, as their performance is comparable.

To explore the compatibility of our reduction process with substrates employed in flexible electronics, the reduction of a film GO deposited on polyethylene terephthalate (PET) is performed using the four reducing agents. As can be seen in Fig. S24 (ESI†), only the CrGO films reduced with AA and  $\text{Na}_2\text{S}_2\text{O}_4$  are stable and homogeneous. Then, the mechanical stability of the films was tested by performing 2000 bending cycles (Fig. S25, ESI†). The resistance of the film was constant for the 2000 bending cycles performed with subtle variations below 1%.

### Electrochemical characterization

The electrochemical performance of all the CrGO samples was evaluated in a symmetrical two-electrode cell using cyclic voltammetry (CV), galvanostatic charge/discharge (GCD) and electrochemical impedance spectroscopy (EIS). Fig. 4(a) and (d) show the CV profiles at a  $2$   $\text{mV s}^{-1}$  scan rate of GO reduced with the different reducing agents at (a) 2 and (d) 12 hours of reaction. As we previously demonstrated, rGO is a pseudocapacitor material that agrees with the obtained quasi-rectangular shaped CVs.<sup>4,57,58</sup> The electrochemical performance can be inferred from the area of the CV plot, providing an initial indication of the most promising samples. In particular,  $\text{rGO}(\text{NaBH}_4)$ , at both 2 and 12 hours of reaction, displays the CVs

with the largest area. Fig. S26 (ESI†) shows the CV profiles at different scan rates of CrGO with different reducing agents at different reaction times. The symmetrical capacitive behavior was maintained up to an ultrafast scan rate of  $2000$   $\text{mV s}^{-1}$ , implying a quick charge propagation within the electrode material.

The pseudocapacitive behavior of CrGO is confirmed by galvanostatic charge/discharge curves, as shown in Fig. 4(b), (e) and Fig. S27 (ESI†). The voltage–time curve exhibits a quasi-linear shape and similar trends to those obtained by CV analysis. The specific capacitances of CrGO were calculated from GCD profiles at different current densities, as shown in Fig. S28 (ESI†) (see the Materials and characterization section, Experimental details subsection for calculation details). The maximum specific capacitance amounts to  $211$   $\text{F g}^{-1}$  for  $\text{rGO}(\text{NaBH}_4)_{12}$  h. From these values two main conclusions can be drawn: (i) the reaction time plays a major role in the obtained specific capacitance of CrGO for the four reducing agents and (ii) the obtained specific capacitances of CrGO are not directly proportional to the strength of the reducing agents employed.

Surface area, porosity, electrical and ionic conductivity and electrochemical activity have been identified as the key properties that strongly influence the electrochemical performance of materials employed as energy storage systems (ESS). The increase in surface area is directly proportional to the electrochemical performance, as a large surface area offers access to abundant active sites for electrochemical reactions or electrostatic interactions.<sup>59</sup> As shown in Fig. S29(a) (ESI†), surface area and capacitance follow nearly the same trend for the different reducing agents and reaction times. High porosity is crucial in faradaic charge transfer processes in pseudocapacitive-type materials and determines the access of the charge transfer active sites and facilitates ion conduction through the electrode material.<sup>60</sup> As in the case of surface area, Fig. S29(b) (ESI†) shows that pore size and capacitance follow the same trend. Higher electrical conductivity facilitates electron migration from electrode materials to current collectors, enabling better rate performance. Fig. S29(c) (ESI†) shows that above a certain threshold (conductivity  $> 20$   $\text{S m}^{-1}$ ) the increase in electrical conductivity is not translated into an increase in capacitance. Ionic conductivity is a critical factor affecting the electrochemical performance of double-layer capacitors and pseudocapacitors. Improved ionic conductivity helps instantaneous polarization across the electrode surface, which permits greater access of the electrolyte ions within a short time. The ionic conductivity of GO and CrGO-based electrodes is obtained using electrochemical impedance spectroscopy (EIS) (see Table S6, ESI†). Fig. S29(d) (ESI†) shows that, except for GO, the ionic conductivity and capacitance follow the same trend. The presence of electrochemically active groups (*e.g.*, OFGs) is advantageous, as they can provide a large additional pseudocapacitance. During the reduction process, OFGs are eliminated and therefore this is detrimental to the electrochemical performance. Fig. S29(e) (ESI†) shows that the two reducing agents that produce CrGO with lower oxygen content (*i.e.*,  $\text{N}_2\text{H}_4$  and  $\text{Na}_2\text{S}_2\text{O}_4$ ) also show the lowest



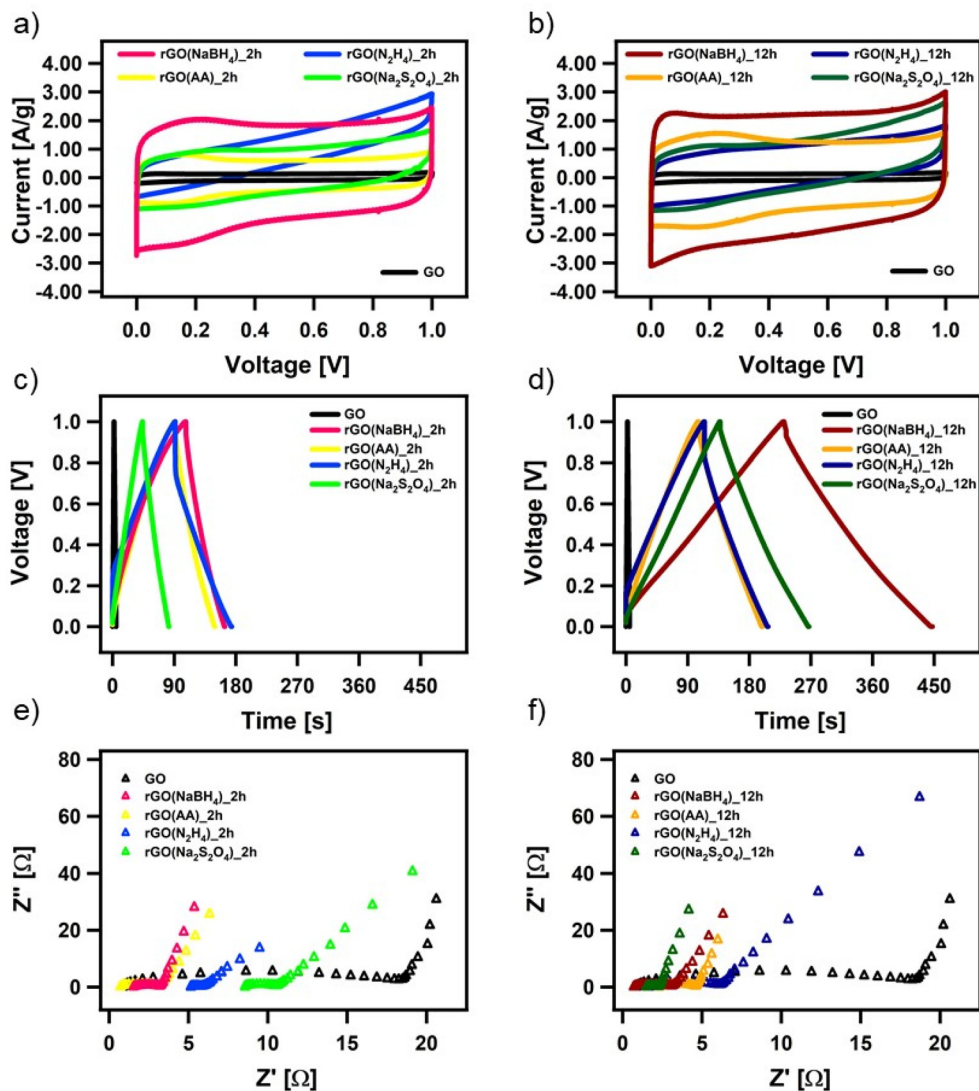


Fig. 4 Electrochemical characterization of chemically reduced GO. (a and b) CV curves at a scan rate of  $5 \text{ mV s}^{-1}$ , (c and d) GCD profiles at a current density of  $1 \text{ A g}^{-1}$  and (e and f) magnification of the high-frequency region of the Nyquist plots.

capacitance values. In contrast, AA and  $\text{NaBH}_4$  produce CrGO with higher oxygen content, but only after 12 hours is the specific capacitance boosted. Pristine GO, despite having the highest amount of OFG, exhibits the lowest capacitance due to its small surface area and poor conductivity.

All CrGO samples show a good rate capability, with a decrease of less than 30% in capacitance at higher current densities. For instance, the capacitance of  $\text{rGO}(\text{NaBH}_4)_{12 \text{ h}}$  is as high as  $169 \text{ F g}^{-1}$  at a high current density of  $20 \text{ A g}^{-1}$ , implying a quick charge propagation. Another important factor affecting the electrochemical performance of supercapacitor devices is the Ohmic drop (IR), which is caused by internal resistance (including the electrolyte resistance, the resistance of the electrode active-material, and the contact resistance between the active materials and the current collector).<sup>61,62</sup> In the case of the  $\text{rGO}(\text{NaBH}_4)$ ,  $\text{rGO}(\text{AA})$ , and  $\text{rGO}(\text{Na}_2\text{S}_2\text{O}_4)$  electrodes, we can observe a very small IR drop ( $\sim 2\text{--}3\%$ ) while the  $\text{rGO}(\text{N}_2\text{H}_4)$

electrodes exhibit a significantly larger IR drop ( $\sim 20\%$ ), which indicates a non-effective discharging process.

Moreover, the EIS data are evaluated by examining the Nyquist plots (shown in Fig. 4(c) and (f)). In an ideal double-layer capacitor, the Nyquist plot should appear as a vertical line running parallel to the imaginary axis. However, the presence of a semicircle at high frequencies indicates the existence of various OFGs on the GO surface, giving rise to a pseudo-capacitive behavior. The experimental results are well-fitted with the indicated circuit (Fig. S30, ESI<sup>†</sup>) and the fitting parameters can be seen in Table S6 (ESI<sup>†</sup>). The low  $R_{\text{ct}}$  values of CrGO are consistent with the fact that at a current density, as high as  $20 \text{ A g}^{-1}$ , a high value of capacitance is still obtained, indicating a good rate capability of the CrGO samples. Besides, among the different CrGO samples,  $\text{rGO}(\text{N}_2\text{H}_4)_{12 \text{ h}}$  shows the highest  $R_{\text{ct}}$ , which is in agreement with the observed largest IR drop.









- 7 Q. Gao, J. Yan, L. Wan, C. Zhang, Z. Wen, X. Zhou, H. Li, F. Li, J. Chen, J. Guo, D. Song, B. S. Flavel and J. Chen, *Adv. Mater. Interfaces*, 2022, **9**, 2201221.
- 8 X.-D. Zhuang, Y. Chen, G. Liu, P.-P. Li, C.-X. Zhu, E.-T. Kang, K.-G. Noeh, B. Zhang, J.-H. Zhu and Y.-X. Li, *Adv. Mater.*, 2010, **22**, 1731–1735.
- 9 C.-B. Huang, S. Witomska, A. Aliprandi, M.-A. Stoeckel, M. Bonini, A. Ciesielski and P. Samori, *Adv. Mater.*, 2019, **31**, 1804600.
- 10 G. Reina, J. M. González-Domínguez, A. Criado, E. Vázquez, A. Bianco and M. Prato, *Chem. Soc. Rev.*, 2017, **46**, 4400–4416.
- 11 B. Fadeel, C. Bussy, S. Merino, E. Vázquez, E. Flahaut, F. Mouchet, L. Evariste, L. Gauthier, A. J. Koivisto, U. Vogel, C. Martín, L. G. Delogu, T. Buerki-Thurnherr, P. Wick, D. Beloin-Saint-Pierre, R. Hirschier, M. Pelin, F. Candotto Carniel, M. Tretiach, F. Cesca, F. Benfenati, D. Scaini, L. Ballerini, K. Kostarelos, M. Prato and A. Bianco, *ACS Nano*, 2018, **12**, 10582–10620.
- 12 F. Bonaccorso, Z. Sun, T. Hasan and A. C. Ferrari, *Nat. Photonics*, 2010, **4**, 611–622.
- 13 H. Yamaguchi, J. Granstrom, W. Nie, H. Sojoudi, T. Fujita, D. Voiry, M. Chen, G. Gupta, A. D. Mohite, S. Graham and M. Chhowalla, *Adv. Energy Mater.*, 2014, **4**, 1300986.
- 14 S. F. Pei and H. M. Cheng, *Carbon*, 2012, **50**, 3210–3228.
- 15 D. Karacic, S. J. Gutic, B. Vasic, V. M. Mirsky, N. V. Skorodumova, S. V. Mentus and I. A. Pasti, *Electrochim. Acta*, 2022, **410**, 11.
- 16 X. Mei and J. Ouyang, *Carbon*, 2011, **49**, 5389–5397.
- 17 F. Iskandar, U. Hikmah, E. Stavila and A. H. Aimon, *RSC Adv.*, 2017, **7**, 52391–52397.
- 18 H. Li and C. Bubeck, *Macromol. Res.*, 2013, **21**, 290–297.
- 19 S. Eigler and A. Hirsch, *Angew. Chem., Int. Ed.*, 2014, **53**, 7720–7738.
- 20 S. Eigler, S. Grimm, M. Enzelberger-Heim, P. Müller and A. Hirsch, *Chem. Commun.*, 2013, **49**, 7391–7393.
- 21 X. Wang, L. Zhi and K. Müllen, *Nano Lett.*, 2008, **8**, 323–327.
- 22 H. J. Sim, Z. Li, P. Xiao and H. Lu, *Molecules*, 2022, **27**, 7840.
- 23 S. Mao, K. Yu, S. Cui, Z. Bo, G. Lu and J. Chen, *Nanoscale*, 2011, **3**, 2849–2853.
- 24 X. Zhou, J. Zhang, H. Wu, H. Yang, J. Zhang and S. Guo, *J. Phys. Chem. C*, 2011, **115**, 11957–11961.
- 25 H. J. Shin, K. K. Kim, A. Benayad, S. M. Yoon, H. K. Park, I. S. Jung, M. H. Jin, H. K. Jeong, J. M. Kim, J. Y. Choi and Y. H. Lee, *Adv. Funct. Mater.*, 2009, **19**, 1987–1992.
- 26 J. L. Zhang, H. J. Yang, G. X. Shen, P. Cheng, J. Y. Zhang and S. W. Guo, *Chem. Commun.*, 2010, **46**, 1112–1114.
- 27 K. K. H. De Silva, H.-H. Huang and M. Yoshimura, *Appl. Surf. Sci.*, 2018, **447**, 338–346.
- 28 M. J. Fernández-Merino, L. Guardia, J. I. Paredes, S. Villar-Rodil, P. Solís-Fernández, A. Martínez-Alonso and J. M. D. Tascón, *J. Phys. Chem. C*, 2010, **114**, 6426–6432.
- 29 L. G. Guex, B. Sacchi, K. F. Peuvot, R. L. Andersson, A. M. Pourrahimi, V. Ström, S. Farris and R. T. Olsson, *Nanoscale*, 2017, **9**, 9562–9571.
- 30 V. Agarwal and P. B. Zetterlund, *Chem. Eng. J.*, 2021, **405**, 127018.
- 31 K. K. H. De Silva, H. H. Huang and M. Yoshimura, *Appl. Surf. Sci.*, 2018, **447**, 338–346.
- 32 C. Bing, Y. Jiahao, L. Xiaoying, J. Qi, W. Guoping and J. Linghua, *Diamond Relat. Mater.*, 2021, **114**, 108305.
- 33 B. G. Rani, M. S. B. Reddy, S. Kailasa, H. Maseed, K. Bikshalu and K. V. Rao, *Mater. Res. Express*, 2019, **6**, 8.
- 34 K. K. H. De Silva, H. H. Huang, R. K. Joshi and M. Yoshimura, *Carbon*, 2017, **119**, 190–199.
- 35 Z. Sui, X. Zhang, Y. Lei and Y. Luo, *Carbon*, 2011, **49**, 4314–4321.
- 36 J. Gao, F. Liu, Y. Liu, N. Ma, Z. Wang and X. Zhang, *Chem. Mater.*, 2010, **22**, 2213–2218.
- 37 Z. S. Wu, K. Parvez, X. Feng and K. Müllen, *Nat. Commun.*, 2013, **4**, 2487.
- 38 F. Bonaccorso, L. Colombo, G. Yu, M. Stoller, V. Tozzini, A. C. Ferrari, R. S. Ruoff and V. Pellegrini, *Science*, 2015, **347**, 1246501.
- 39 Z. Li, S. Gadipelli, Y. Yang, G. He, J. Guo, J. Li, Y. Lu, C. A. Howard, D. J. L. Brett, I. P. Parkin, F. Li and Z. Guo, *Energy Storage Mater.*, 2019, **17**, 12–21.
- 40 S. Sarr, N. F. Sylla, D. T. Bakhoun, N. M. Ndiaye, D. J. Tarimo, V. M. Maphiri, B. D. Ngom and N. Manyala, *J. Energy Storage*, 2022, **55**, 105666.
- 41 P. Bharathidasan, M. B. Idris, D.-W. Kim, S. R. Sivakkumar and S. Devaraj, *FlatChem*, 2018, **11**, 24–31.
- 42 T. Zhou, F. Chen, C. Tang, H. Bai, Q. Zhang, H. Deng and Q. Fu, *Compos. Sci. Technol.*, 2011, **71**, 1266–1270.
- 43 J. Molina, J. Fernández, A. I. del Río, J. Bonastre and F. Cases, *Appl. Surf. Sci.*, 2013, **279**, 46–54.
- 44 C. Xu, X. Shi, A. Ji, L. Shi, C. Zhou and Y. Cui, *PLoS One*, 2015, **10**, e0144842.
- 45 I. Bertóti, S. Farah, A. Bulátkó, A. Farkas, J. Madarász, M. Mohai, G. Sáfrán and K. László, *Carbon*, 2022, **199**, 415–423.
- 46 S. Park, Y. Hu, J. O. Hwang, E.-S. Lee, L. B. Casabianca, W. Cai, J. R. Potts, H.-W. Ha, S. Chen, J. Oh, S. O. Kim, Y.-H. Kim, Y. Ishii and R. S. Ruoff, *Nat. Commun.*, 2012, **3**, 638.
- 47 A. Y. Lee, K. Yang, N. D. Anh, C. Park, S. M. Lee, T. G. Lee and M. S. Jeong, *Appl. Surf. Sci.*, 2021, **536**, 147990.
- 48 S. Claramunt, A. Varea, D. López-Díaz, M. M. Velázquez, A. Cornet and A. Cirera, *J. Phys. Chem. C*, 2015, **119**, 10123–10129.
- 49 F. Tuinstra and J. L. Koenig, *Chem. Phys.*, 1970, **53**, 1126–1130.
- 50 A. C. Ferrari, J. C. Meyer, V. Scardaci, C. Casiraghi, M. Lazzeri, F. Mauri, S. Piscanec, D. Jiang, K. S. Novoselov, S. Roth and A. K. Geim, *Phys. Rev. Lett.*, 2006, **97**, 187401.
- 51 L. G. Cançado, A. Jorio, E. H. M. Ferreira, F. Stavale, C. A. Achete, R. B. Capaz, M. V. O. Moutinho, A. Lombardo, T. S. Kulmala and A. C. Ferrari, *Nano Lett.*, 2011, **11**, 3190–3196.
- 52 A. Y. Lee, K. Yang, N. D. Anh, C. Park, S. M. Lee, T. G. Lee and M. S. Jeong, *Appl. Surf. Sci.*, 2021, **536**, 147990.



- 53 A. Eckmann, A. Felten, A. Mishchenko, L. Britnell, R. Krupke, K. S. Novoselov and C. Casiraghi, *Nano Lett.*, 2012, **12**, 3925–3930.
- 54 D. López-Díaz, M. López Holgado, J. L. García-Fierro and M. M. Velázquez, *J. Phys. Chem. C*, 2017, **121**, 20489–20497.
- 55 T. Zhou, F. Chen, K. Liu, H. Deng, Q. Zhang, J. Feng and Q. Fu, *Nanotechnology*, 2010, **22**, 045704.
- 56 B. Lesiak, G. Trykowski, J. Tóth, S. Biniak, L. Kövér, N. Rangam, L. Stobinski and A. Malolepszy, *J. Mater. Sci.*, 2021, **56**, 3738–3754.
- 57 T. Lv, M. Liu, D. Zhu, L. Gan and T. Chen, *Adv. Mater.*, 2018, **30**, 1705489.
- 58 Y. Bai, R. B. Rakhi, W. Chen and H. N. Alshareef, *J. Power Sources*, 2013, **233**, 313–319.
- 59 L. Zhang, X. Yang, F. Zhang, G. Long, T. Zhang, K. Leng, Y. Zhang, Y. Huang, Y. Ma, M. Zhang and Y. Chen, *J. Am. Chem. Soc.*, 2013, **135**, 5921–5929.
- 60 Y. Zhu, S. Murali, M. D. Stoller, K. J. Ganesh, W. Cai, P. J. Ferreira, A. Pirkle, R. M. Wallace, K. A. Cychosz, M. Thommes, D. Su, E. A. Stach and R. S. Ruoff, *Science*, 2011, **332**, 1537–1541.
- 61 Y. Xu, Z. Lin, X. Huang, Y. Wang, Y. Huang and X. Duan, *Adv. Mater.*, 2013, **25**, 5779–5784.
- 62 K. Yang, K. Cho, D. S. Yoon and S. Kim, *Sci. Rep.*, 2017, **7**, 40163.
- 63 C. Xu, B. Xu, Y. Gu, Z. Xiong, J. Sun and X. S. Zhao, *Energy Environ. Sci.*, 2013, **6**, 1388–1414.
- 64 S. Zhao, Z. Song, L. Qing, J. Zhou and C. Qiao, *J. Phys. Chem. C*, 2022, **126**, 9248–9256.
- 65 L. Fusco, M. Garrido, C. Martín, S. Sosa, C. Ponti, A. Centeno, B. Alonso, A. Zurutuza, E. Vázquez, A. Tubaro, M. Prato and M. Pelin, *Nanoscale*, 2020, **12**, 610–622.
- 66 E. Corsini and C. L. Galli, *Toxicol. Lett.*, 1998, **102–103**, 277–282.
- 67 A. Dalla Colletta, M. Pelin, S. Sosa, L. Fusco, M. Prato and A. Tubaro, *Carbon*, 2022, **196**, 683–698.
- 68 M. Pelin, L. Fusco, C. Martín, S. Sosa, J. Frontinan-Rubio, J. M. Gonzalez-Dominguez, M. Duran-Prado, E. Vazquez, M. Prato and A. Tubaro, *Nanoscale*, 2018, **10**, 11820–11830.
- 69 J. Frontinan-Rubio, M. V. Gomez, C. Martín, J. M. Gonzalez-Dominguez, M. Duran-Prado and E. Vazquez, *Nanoscale*, 2018, **10**, 11604–11615.
- 70 T. Pulingam, K. L. Thong, J. N. Appaturi, C. W. Lai and B. F. Leo, *Chemosphere*, 2021, **281**, 11.
- 71 J. Frontinan-Rubio, M. V. Gomez, V. J. Gonzalez, M. Duran-Prado and E. Vazquez, *Sci. Rep.*, 2020, **10**, 17.
- 72 L. Fusco, M. Pelin, S. Mukherjee, S. Keshavan, S. Sosa, C. Martín, V. Gonzalez, E. Vazquez, M. Prato, B. Fadeel and A. Tubaro, *Carbon*, 2020, **159**, 598–610.
- 73 S. Sosa, A. Tubaro, M. Carlin, C. Ponti, E. Vazquez, M. Prato and M. Pelin, *NanoImpact*, 2023, **29**, 9.
- 74 H. Kim, J. Choi, H. Lee, J. Park, B. I. Yoon, S. M. Jin and K. Park, *Toxicol. Res.*, 2016, **32**, 311–316.

